

AMENDMENT

In the claims:

Please amend claims 1, 7, 13, and 19 as follows:

1. (Twice Amended) A device for generating a plurality of electron beams comprising:
- a) a source of radiation;
 - b) a spatial light modulator having a position so as to modulate said radiation emanating from said source of radiation; and
 - c) a photocathode having a position so as to receive said modulated radiation wherein said photocathode simultaneously produces a plurality of electron beams under impact by said modulated radiation as result of said modulation of the radiation by the spatial light modulator.

7. (Twice Amended) An electron beam lithography system comprising:
- a) a source of radiation;
 - b) a spatial light modulator having a position so as to modulate said radiation emanating from said source of radiation;
 - c) a photocathode having a position so as to receive said modulated radiation wherein said photocathode simultaneously produces a plurality of electron beams under impact by said modulated radiation as result of said modulation of the radiation by the spatial light modulator; and
 - d) an electron beam optical column having a position so as to receive said plurality of electron beams and to direct said plurality of electron beams onto a target.

13. (Twice Amended) A method of producing a plurality of electron beams comprising:

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- a) directing radiation onto a spatial light modulator, thereby modulating said radiation; and
 - b) directing said modulated radiation onto a photocathode thereby simultaneously producing a plurality of electron beams as result of said modulation of the radiation by the spatial light modulator.

19. (Twice Amended) A method of performing lithography with multiple beams of electrons comprising:

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- a) directing radiation onto a spatial light modulator, thereby modulating said radiation;
 - b) directing said modulated radiation onto a photocathode thereby simultaneously producing a plurality of electron beams as result of said modulation of the radiation by the spatial light modulator; and
 - c) directing said plurality of electron beams onto an acceptance region of an electron beam optical column, producing thereby a plurality of electron beams impacting a target located at the target end of said electron beam optical column.